

## ENABLING CHAIN SCISSION OF BRANCHED PHOTORESIST

### Abstract of the Disclosure

By using a branched long chained chain scission  
polymer as a photoresist for EUV and 157 nanometer  
5 applications, a relatively higher molecular weight polymer  
with good mechanical properties may be achieved. In  
addition, by using chain scission technology, line edge  
roughness and resolution may be improved at the same time.